



INFORMATION DISCLOSURE STATEMENT PTO-1449	Attv. Docket No. 042183	Serial No. <u>101797,723</u> New Appln
	Applicant(s): Katsunori ICHIKI et al.	
	Filing Date: March 11, 2004	Group Art Unit: <u>2881</u>



U.S. PATENT DOCUMENTS

Examiner Initial		Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
	AA	4,158,589	Keller et al.	06/19/79			
	AB	5,827,435	Samukawa	10/27/98			
	AC	5,928,528	Kubota et al.	07/27/99			
	AD	6,217,703	Kitagawa	04/17/01			
	AE	6,331,701	Chen et al.	12/18/01			

FOREIGN PATENT DOCUMENTS

		Document No.	Date	Country	Translation (Yes or No)
	AF	WO 01/06534	01/25/01	PCT	Abstract
	AG	WO 02/078407	10/03/02	PCT	Abstract

OTHER DOCUMENTS

	AH	J.M.E. Harper et al., "Low Energy Ion Beam Etching", J. Electrochem. Soc: SOLID-STATE SCIENCE AND TECHNOLOGY, Vol.128, No. 5, May 1981, pp. 1077-1083.
	AI	Harold R. Kaufman, "Technology of ion beam sources used in sputtering", J. Vac. Sci. Technol. 15(2), March/April 1978, pp. 272-276.
	AJ	Shoji KITAMURA, "Ion Engine (Direct Current Discharge Type)", J. Vac. Soc. Jpn. Vol. 45, No. 4, 2002, pp. 329-335.
Examiner 	Date Considered <u>07/05/05</u>	